



Atomic Layer Deposition (ALD): Equipment: TFS 200, BENEQ: Atomic Layer Deposition (ALD), as a thin film coating method, offers:

- ✓ Precise control of the film thickness, at true nanometer scale
- ✓ Pinhole-free films
- ✓ Conformal coating of large-area substrates and complex 3D objects
- ✓ A highly repeatable and scalable process